L Number	Hits	Search Text	DB	Time stamp
1	5295	(250/492.2,504R,492.1).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 00:57
2	3764	(extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 00:58
3	2517	((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern$4 near1 structure))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:45
4	494	(((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern$4 near1 structure))) and (by-product$4 or pollut$5 or contamin$4 or debris)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:46
5	480	((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern$4 near1 structure))) and (by-product$4 or pollut$5 or contamin$4 or debris)) and (substrate or wafer or sample)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:01
6	380	(((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern$4 near1 structure))) and (by-product$4 or pollut$5 or contamin$4 or debris)) and (substrate or wafer or sample)) and project$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:01
7	111	((((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern$4 near1 structure))) and (by-product$4 or pollut$5 or contamin$4 or debris)) and (substrate or wafer or sample)) and project$5) and electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:01
8	74	(((((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern$4 near1 structure))) and (by-product$4 or pollut$5 or contamin$4 or debris)) and (substrate or wafer or sample)) and project$5) and electrode) and collect$8	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:02
9	12	((((((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern$4 near1 structure))) and (by-product$4 or pollut$5 or contamin$4 or debris)) and (substrate or wafer or sample)) and project$5) and electrode) and collect$8) and (collect$4 with (by-product$4 or pollut$5 or contamin$4 or debris))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:47
10	222	((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and ((250/492.2,504R,492.1).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:45

11	193	(((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and ((250/492.2,504R,492.1).CCLS.)) and (mask or reticle or (pattern$4 near1 structure))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:46
12	79	((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and ((250/492.2,504R,492.1).CCLS.)) and (mask or reticle or (pattern$4 near1 structure))) and (by-product$4 or pollut$5 or contamin$4 or debris)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:46
13	4	((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and ((250/492.2,504R,492.1).CCLS.)) and (mask or reticle or (pattern$4 near1 structure))) and (by-product$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 01:46
14	36	((((((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern$4 near1 structure))) and (by-product$4 or pollut$5 or contamin$4 or debris)) and (substrate or wafer or sample)) and project$5) and electrode) and collect$8) and (plasma with (by-product$4 or pollut$5 or contamin$4 or debris))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 02:28
15	14	(((((((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern$4 near1 structure))) and (by-product$4 or pollut$5 or contamin$4 or debris)) and (substrate or wafer or sample)) and project$5) and electrode) and collect$8) and (plasma with (by-product$4 or pollut$5 or contamin$4 or debris))) and ((250/492.2,504R,492.1).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 02:29
16	3	(((((((((extreme adj ultraviolet) or EUV or extreme-ultraviolet or (extreme adj ultra-violet)) and (mask or reticle or (pattern$4 near1 structure))) and (by-product$4 or pollut$5 or contamin$4 or debris)) and (substrate or wafer or sample)) and project$5) and electrode) and collect$8) and (plasma with (by-product$4 or pollut$5 or contamin$4 or debris))) and (particle with mov$6)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/09/26 02:29

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